




*14th International Conference  
on Atomic Layer Deposition (ALD2014)*

*Poster Award*

*is hereby awarded to the excellent paper,  
Influence of Al<sub>2</sub>O<sub>3</sub> gate insulators deposited by  
PE-ALD method in electrical properties of IGZO-TFT  
By K. Kurishima, T. Nabatame, M. Shimizu, S. Aikawa,  
K. Tsukagoshi, A. Ohi, T. Chikyow and A. Ogura,  
(Japan)*

*in recognition of the distinguished contribution to  
14th International Conference  
on Atomic Layer Deposition (ALD 2014)  
June 17th, 2014, Kyoto, Japan*

  
*Yukihiro Shimogaki*  
Co-Chair,  
ALD2014 Organizing Committee  
(The University of Tokyo)

  
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